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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Chiang, Tony P.; Leaser, Karl F.

Assignee: Novellus Systems, Inc. (reassigned)

Title: Method and Apparatus for Improved Temperature Control In Atomic Layer Deposition

Serial No.: 09/854,092

Filing Date: May 10, 2001

Examiner: Timothy Meeks

Group Art Unit: 1762

Docket No.: ANG-PA-1663 US

San Jose, California  
September 28, 2004Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450RESPONSE TO OFFICE ACTION

Dear Sir:

This responds to the Office Action dated July 7, 2004, in the above-identified application. Please amend the application as follows.

Amendments to the specification begin on page 2.

Amendments to the claims begin on page 3.

Remarks begin on page 10.

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Ser. No. 09/854,092

Please amend paragraph [0001] as follows:

This application is a Continuation-In-Part of U.S. Patent Application Serial Nos. 09/812,285, now U.S. Patent No. 6,428,859, 09/812,352, now abandoned, and 09/812,486, now U.S. Patent No. 6,416,822, all filed March 19, 2001, and incorporated herein by reference. This application claims the benefit of U.S. Provisional Application No. 60/251,795, filed December 6, 2000, and U.S. Provisional Application No. 60/254,280, filed December 6, 2000 and ~~U.S. Utility Application Nos. 09/812,285, 09/812,352, and 09/812,486; all filed March 19, 2001.~~